

Electronic Supplementary Material

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Fabrication of Nanochannels via Near-Field Electrospinning

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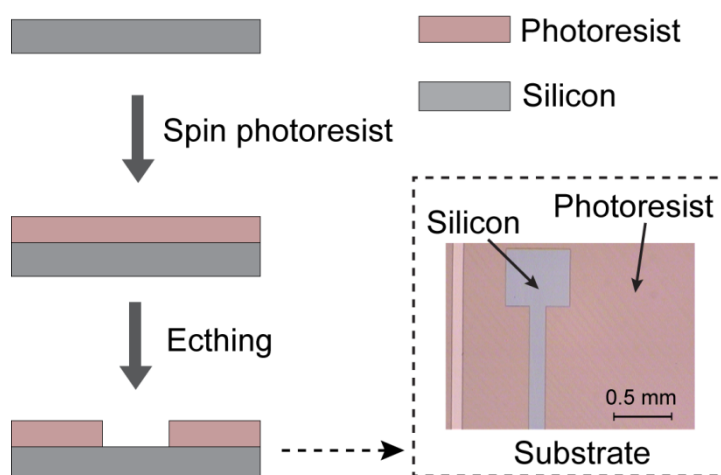


Fig. S1 Fabrication processes for a pre-patterned silicon substrate where the Au coating area is defined.

The thickness of photoresist is about several hundred nanometers.